

二次谐波光谱简介

陈帅宇 2101110181



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Introduction

- Second Harmonic Generation (SHG) 吸收基频光并放出倍频光的非线性光学效应→材料的性质蕴含在响应系数之中
- 对称性破缺、序参量、相变
- 自发极化场分布



SHG的基本描述

• 唯象描述:

$$\overrightarrow{S} = \mu_0 \frac{\partial^2 \overrightarrow{P}}{\partial t^2} + \mu_0 \left(\nabla \times \frac{\partial \overrightarrow{M}}{\partial t} \right) - \mu_0 \left(\nabla \frac{\partial^2 \overrightarrow{Q}}{\partial t^2} \right) + \cdots$$

S: source term of radiated light

P: electric dipole

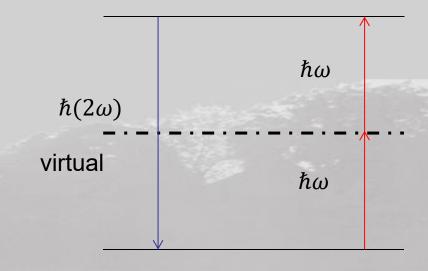
M : magnetic dipole

Q : electric quadrupole

$$\overrightarrow{P}(\omega, 2\omega, ...) \propto \chi^{pe} \overrightarrow{E}(\omega) + \chi^{pm} \overrightarrow{H}(\omega) + \chi^{pee} \overrightarrow{E}(\omega) \overrightarrow{E}(\omega) + \chi^{pem} \overrightarrow{E}(\omega) \overrightarrow{H}(\omega) + \chi^{pmm} \overrightarrow{H}(\omega) \overrightarrow{H}(\omega) + \mathcal{O}\left[\left(\overrightarrow{E}, \overrightarrow{H}\right)^{3}\right]$$

$$\overrightarrow{M}(\omega, 2\omega, ...) \propto \chi^{me} \overrightarrow{E}(\omega) + \chi^{mm} \overrightarrow{H}(\omega) + \chi^{mee} \overrightarrow{E}(\omega) \overrightarrow{E}(\omega) + \chi^{mem} \overrightarrow{E}(\omega) \overrightarrow{H}(\omega) + \chi^{mmm} \overrightarrow{H}(\omega) \overrightarrow{H}(\omega) + \mathcal{O}\left[\left(\overrightarrow{E}, \overrightarrow{H}\right)^{3}\right]$$

$$\overrightarrow{Q}(\omega, 2\omega, ...) \propto \chi^{qe} \overrightarrow{E}(\omega) + \chi^{qm} \overrightarrow{H}(\omega) + \chi^{qee} \overrightarrow{E}(\omega) \overrightarrow{E}(\omega) + \chi^{qem} \overrightarrow{E}(\omega) \overrightarrow{H}(\omega) + \chi^{qmm} \overrightarrow{H}(\omega) \overrightarrow{H}(\omega) + \mathcal{O}\left[\left(\overrightarrow{E}, \overrightarrow{H}\right)^{3}\right]$$



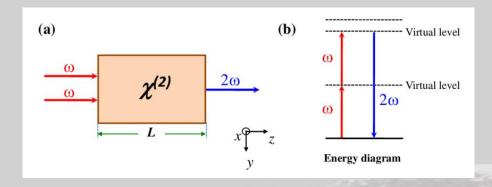
一种粗糙的量子的理解

• 量子描述: 电偶极近似、拓扑、Berry connection......

常被考虑的两类SHG

$$P_i(2\omega) = \chi_{ijk}^{ED} E_j(\omega) E_k(\omega)$$

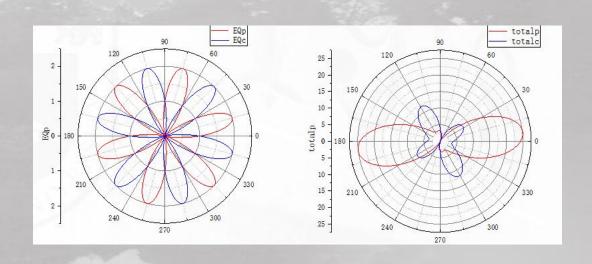
$$P_i(2\omega) \propto \chi_{ijkl}^{EQ} E_j(\omega) \nabla_k E_l(\omega)$$



若体系有反演对称性,则此项必为0

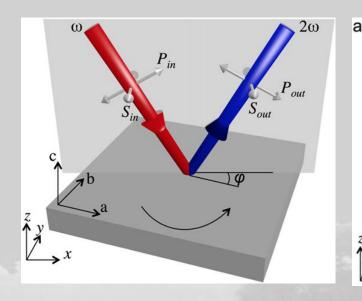
• 与对称性的联系

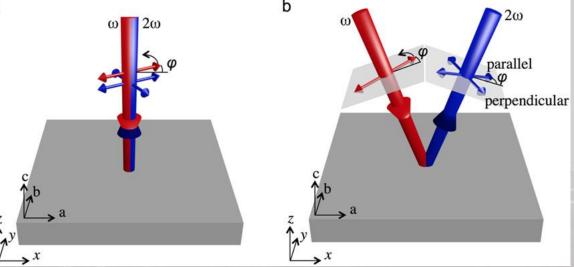
$$\chi_{ijk...} = R_{ii'}R_{jj'}R_{kk'}\cdots\chi_{ij'k'...}$$

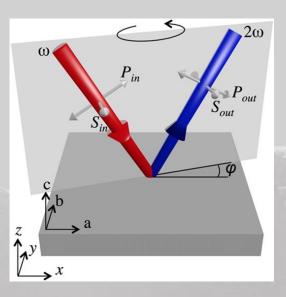




SHG的实验配置



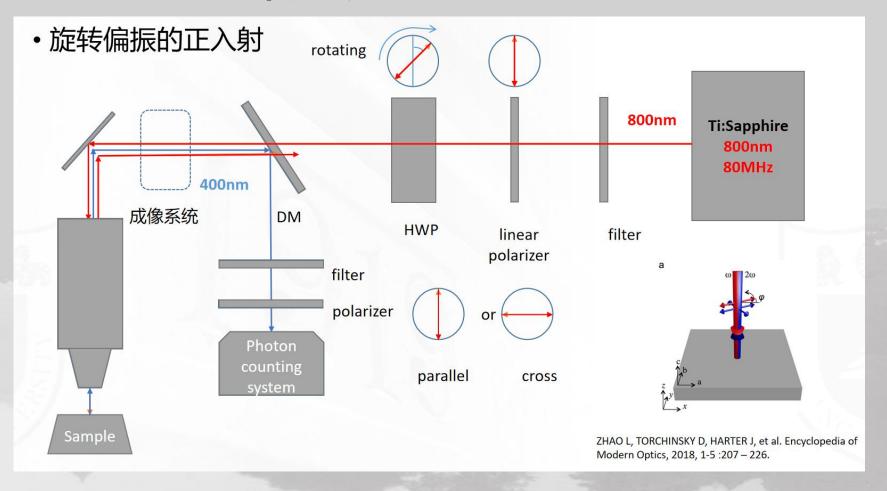




ZHAO L, TORCHINSKY D, HARTER J, et al. Encyclopedia of Modern Optics, 2018, 1-5:207 – 226.



SHG的一种实验光路



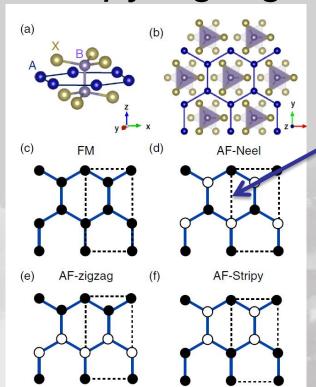


SHG在揭示材料对称性方面的应用

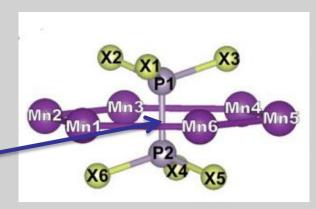
- "A cornerstone in condensed matter research is the emergence of the concept of symmetry and symmetry breaking upon an order formation, an idea that an ordered state can only have a true subset of symmetries of its unordered counterpart"
- 通过SHG可以检验材料的(磁)点群
- 通过改变T、B等外参量,SHG信号形状的变化→对称性变化→可能的相变



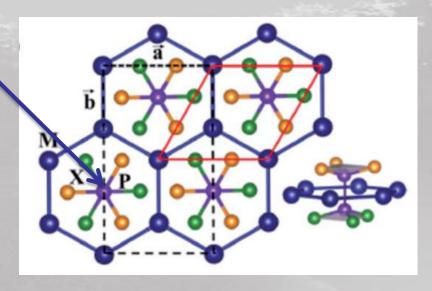
- MPX3家族,理论预言二维磁序:
- FM,stripy,zigzag,Neel







YANG S, ZHANG T, JIANG C. Advanced Science, 2021,2002488: 1 – 31

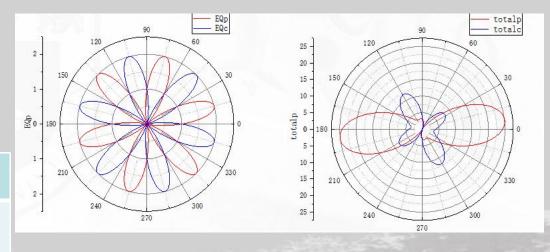


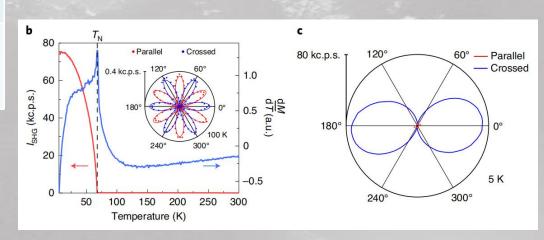
SAMAL R, SANYAL G, CHAKRABORTY B, et al. Journal of Materials Che 2021 : 2560 – 2591



块材点群S₆,空间群148(R3)

	T>T _N	T <t<sub>N</t<sub>
对称性	有三重轴 有反演对称性	晶格有三重轴 无反演对称性
SHG响应	电四极响应	电四极+电偶极







EFI-SHG

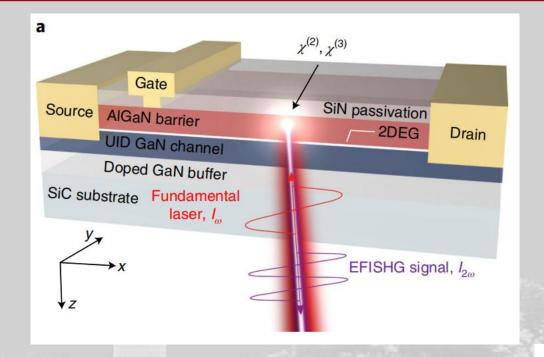
- Electric field mapping of wide-bandgap semiconductor devices at a submicrometre resolution (Nature Electronics, 2021)
- Electric-field-induced SHG 可用于以亚微米精度刻画GaN HEMT的电场分布
- 研究驱动: AIGaN中的强电场可能影响HEMT器件的退化效应(degradation)以及其他器件性能。
- 关注点:通过EFISHG测量,可以得到空间分辨的Ex电场分布
 - 通过证明器件微小的掺杂变化将带来巨大的电场分布变化证明方法的有效性,也和软件模拟的结果相吻合



EFI-SHG

$$P_i(2\omega) = \chi_{ijk}^{ED} E_j(\omega) E_k(\omega)$$

- 通常的SHG由二阶张量刻画,是二阶非线性效应
- EFI-SHG可以理解为电场、两个基频光子的三阶非线性效应。 $P_i^{EFISHG}(2\omega) = \chi_{ijkl}^{(3)}(-2\omega,\omega,\omega,0)E_j(\omega)E_k(\omega)E_l(0)$
- 在中心反演对称的体系,如Si中,EFI-SHG较容易被应用于测量,因主导项电偶极SHG消失。
- · GaN不具有中心反演对称性,因此要考虑两项的相干叠加。
 - 但也有好处,宽禁带使得测量体内的SHG信号变为可能



入射激光x方向线偏振,波矢主要在z 方向(从衬底入射),测量反射信号

基频800nm,倍频光400nm,4H-SiC 衬底375nm,GaN 365nm AlGaN/GaN 6-mm点群 具有四个独立二阶张量元和十个独立三阶张量元他们的实验限定了入射光和反射光的偏振都为x方向,但是聚焦造成了一定的z分量

通过对称性分析, 忽略贡献较小的分量后得到

$$I_{2\omega} \propto \left| P_{2\omega}^0 + P_{2\omega}^{\mathrm{EFISHG}} \right|^2 \propto \left| 2\chi_{xzx}^{(2)} E_{z,\omega} E_{x,\omega} + 3\chi_{xxxx}^{(3)} E_{x,\omega} E_{x,\omega} E_{x} \right|^2$$

不过在实际处理中他们忽略了交叉项

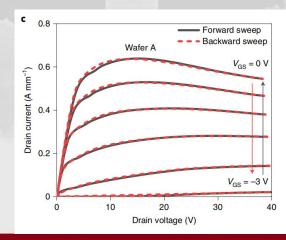


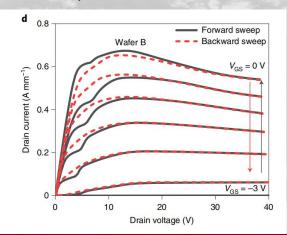
$$I_{2\omega} \propto \left| P_{2\omega}^0 + P_{2\omega}^{\mathrm{EFISHG}} \right|^2 \propto \left| 2\chi_{xzx}^{(2)} E_{z,\omega} E_{x,\omega} + 3\chi_{xxxx}^{(3)} E_{x,\omega} E_{x,\omega} E_{x} \right|^2$$

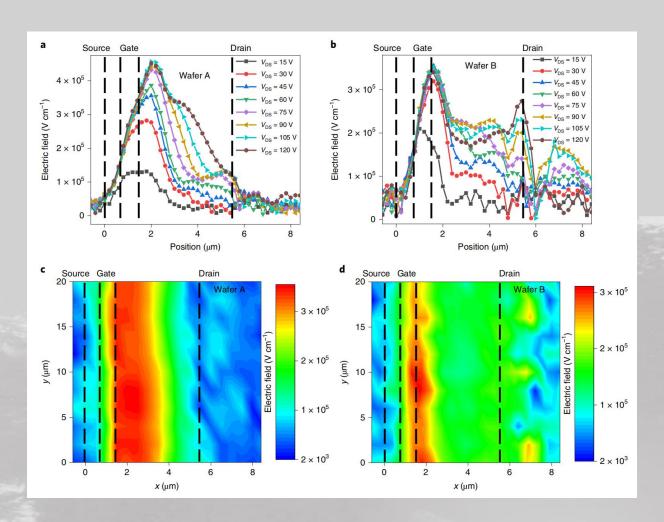
$$E_x = \alpha \left(\sqrt{I_{2\omega} - I_{2\omega}(E_x = 0)} \right)$$

E_x=0是从没有外加偏压的情况下得到的,α是有效光探测效率,可以通过E_x在D-S之间的积分作为约束条件求出

两块不同C掺杂样品→ 4x10¹⁶ for A, 3±1x10¹⁷ for B









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